

INFORMATION DISCLOSURE STATEMENT BY APPLICANTS PTO FORM 1449	Atty. Docket No. 10191/1993	Serial No. 09/914404 To Be Assigned
	Applicant(s) SPITZ et al.	
	Filing Date Herewith 12/13/01	Group 2823 To Be Assigned

U. S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE
<i>ME</i>	3,914,138*	Oct. 21, 1975	Rai-Choudhury Prosenjit	—	—	
<i>ME</i>	4,092,185*	May 30, 1978	Richer John Wilfred	—	—	

* Copy of reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB-CLASS	TRANSLATION	
						YES	NO
	38 15 615*	Nov. 16, 1989	Germany				X
	2-145-772*	Feb. 23, 1973	France				X

* Copy of reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).

OTHER DOCUMENTS

EXAMINER'S INITIALS	AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.
<i>ME</i>	F. Pintchovski et al., "The effect of ambient and time on the diffusion of Antimony in silicon from a doped glass source," Extended Abstracts, vol. 81-2, Oct. 1981 (1981-10), pp. 949-950, XP002149109, Electrochemical Society, Princeton, NJ, US, ISSN: 0160-4619.*
<i>ME</i>	W. Kern et al., "Chemically vapor-deposited borophosphosilicate glasses for silicon device applications," RCA Review, Sept. 1982, USA, vol. 43, no. 3, pp. 423-457, XP002149110, ISSN: 0033-6831.*
<i>ME</i>	V.P. Sundersingh et al., "Concentration profiling for high voltage p/sup +/-n-n/sup +/- diodes," International Journal Of Electronics, Jan. 1983, UK, vol. 54, no. 1, pp. 127-137, XP002149111, ISSN: 0020-7217, pg. 137.*

* Copy of reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).

EXAMINER <i>Michelle Estrada</i>	DATE CONSIDERED 5/10/02
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	